-- In accordance with a second aspect, the present invention provides a method for correcting exposure data for drawing a pattern on an object to be exposed by a plurality of charged particle beams, comprising the step of creating standard dose data for each irradiation position of the charged particle beams in order to expose a standard pattern on the object to be exposed; the step of creating or renewing a plurality of proximity effect correction data for each irradiation position, depending on conditions of the object to be exposed; the step of selecting any one piece of the proximity effect correction data, from plural pieces of the proximity effect correction data for each irradiation position; the step of performing a proximity effect correction with respect to the standard dose data based on the selected data, and exposing a pattern on the object to be exposed; the step of evaluating the exposed pattern, and judging whether the selected one piece of proximity effect correction data is the optimum data for controlling the standard dose data; the step of determining the optimum proximity effect correction data for controlling the standard dose data in accordance with the judgment; the step of measuring, by a sensor, the irradiation dose of the charged particle beams from each element electron optical system, the irradiation dose having been subjected to a correction by the proximity effect correction data; and the step of determining the calibration data of each of the element electron optical systems, based on the irradiation dose measured by the above-mentioned measuring. --

Please substitute the paragraph beginning at page 7, line 25, and ending on page 8, line 3, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

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